L Number	Hits	Search Text	DB	Time stamp
1	116440	wafer	USPAT	2004/04/30 15:14
2	60050	photoresist	USPAT	2004/04/30 15:14
3 .	146708	etching	USPAT	2004/04/30 15:14
4	14973	(monitor\$3 or determin\$6 or indicat\$3 or detect\$3) with (contamination	USPAT	2004/04/30 18:42
→	14775	or (dynamic adj particles) or pollut\$3)		
_	20000	(count\$3 or measur\$3) with ((dynamic adj particles) or particle)	USPAT	2004/04/30 19:53
5	39898	(counts) or measures) with ((dynamic adj particles) or particle)		
6	3047	((silicon adj nitride) or (silicon adj oxide) or (silicon adj oxynitride) or	USPAT	2004/04/30 18:56
		polysilicon) adj2 etching		
7.	0	wafer and photoresist and etching and ((monitor\$3 or determin\$6 or	USPAT	2004/04/30 15:18
		indicat\$3 or detect\$3) with (contamination or (dynamic adj particles) or		
		pollut\$3)) and ((count\$3 or measur\$3) with ((dynamic adj particles) or		
		particle)) and (((silicon adj nitride) or (silicon adj oxide) or (silicon adj		
		oxynitride) or polysilicon) adj2 etching)		
o	10981	wafer with photoresist	USPAT	2004/04/30 15:18
8		(wafer with photoresist) and ((monitor\$3 or determin\$6 or indicat\$3 or	USPAT	2004/04/30 15:18
9	63		USIAI	2004/04/30 13.18
		detect\$3) with (contamination or (dynamic adj particles) or pollut\$3))		
		and ((count\$3 or measur\$3) with ((dynamic adj particles) or particle))		
10	0	((wafer with photoresist) and ((monitor\$3 or determin\$6 or indicat\$3 or	USPAT	2004/04/30 15:19
		detect\$3) with (contamination or (dynamic adj particles) or pollut\$3))		
		and ((count\$3 or measur\$3) with ((dynamic adj particles) or particle)))		
	•	and (((silicon adj nitride) or (silicon adj oxide) or (silicon adj		
		oxynitride) or polysilicon) adj2 etching)		
11	23210	((silicon adj nitride) or (silicon adj oxide) or (silicon adj oxynitride) or	USPAT	2004/04/30 18:17
11	23210		OBIAI	2004/04/30 10:17
		polysilicon) with etching	HODAT	2004/04/20 16:17
12	4	((wafer with photoresist) and ((monitor\$3 or determin\$6 or indicat\$3 or	USPAT	2004/04/30 16:17
		detect\$3) with (contamination or (dynamic adj particles) or pollut\$3))		
		and ((count\$3 or measur\$3) with ((dynamic adj particles) or particle)))		
		and (((silicon adj nitride) or (silicon adj oxide) or (silicon adj		
		oxynitride) or polysilicon) with etching)		
13	250	((count\$3 or measur\$3) with ((dynamic adj particles) or particle)) and	USPAT	2004/04/30 15:47
	250	(wafer with photoresist)		
14	1	(((count\$3 or measur\$3) with ((dynamic adj particles) or particle)) and	USPAT	2004/04/30 15:47
14	4		USFAI	2004/04/30 13.47
		(wafer with photoresist)) and (((silicon adj nitride) or (silicon adj oxide)		
		or (silicon adj oxynitride) or polysilicon) adj2 etching)		
15	340	15.ti,ab,clm.	USPAT	2004/04/30 16:17
16	0	(wafer with photoresist) and 15.ti,ab,clm. and (((silicon adj nitride) or	USPAT	2004/04/30 16:18
		(silicon adj oxide) or (silicon adj oxynitride) or polysilicon) with		
		etching)		
17	0	(wafer with photoresist) and 15.ti,ab,clm.	USPAT	2004/04/30 16:18
18 -	6	15.ti,ab,clm. and photoresist	USPAT	2004/04/30 16:18
			USPAT	2004/04/30 18:27
19	5859	((count\$3 or measur\$3) with ((dynamic adj particles) or	USPAI	2004/04/30 18.2
		particle)).ti,ab,clm.	TTOP: T	0004/04/55
20	1.708_	-((monitor\$3-or-determin\$6-or-indicat\$3-or-detect\$3)-with (contamination	_USPAT	2004/04/30_16:20
		or (dynamic adj particles) or pollut\$3)).ti,ab,clm.		
21	2	(((monitor\$3 or determin\$6 or indicat\$3 or detect\$3) with	USPAT	2004/04/30 18:16
		(contamination or (dynamic adj particles) or pollut\$3)).ti,ab,clm.) and		
		(wafer with photoresist) and ((count\$3 or measur\$3) with ((dynamic adj		
		particles) or particle))		
22		(((count\$3 or measur\$3) with ((dynamic adj particles) or	USPAT	2004/04/30 19:50
32	0		USFAI	2004/04/30 13.30
		particle)).ti,ab,clm.) and (((silicon adj nitride) or (silicon adj oxide) or	· ·	
		(silicon adj oxynitride) or polysilicon) adj2 etching)		
34	2	((((count\$3 or measur\$3) with ((dynamic adj particles) or	USPAT	2004/04/30 18:2
		particle)).ti,ab,clm.) and (((silicon adj nitride) or (silicon adj oxide) or		
		(silicon adj oxynitride) or polysilicon) with etching)) and photoresist		
33	10	(((count\$3 or measur\$3) with ((dynamic adj particles) or	USPAT	2004/04/30 18:29
	. '	particle)).ti,ab,clm.) and (((silicon adj nitride) or (silicon adj oxide) or		
	_	(silicon adj oxynitride) or polysilicon) with etching)	TIODAT	2004/04/20 10 4
35	0	(monitor\$3 or determin\$6 or indicat\$3 or detect\$3) with (contamination	USPAT	2004/04/30 18:42
		or (dynamic adj particles) or pollut\$3) and 5837094.pn.		
36	0	((silicon adj nitride) or (silicon adj oxide) or (silicon adj oxynitride) or	USPAT	2004/04/30 18:5
		polysilicon) and 6254398.pn.		1
		porysmcom and 6254598.pm.		i
37	2	(("3406289") or ("4571079")).PN.	USPAT	2004/04/30 19:34

39		10	(wafer adj scanner).ti,ab,clm.	USPAT	2004/04/30 19:36
41		1	((wafer adj scanner).ti,ab,clm.) and ((count\$3 or measur\$3) with	USPAT	2004/04/30 19:37
			((dynamic adj particles) or particle))		200 110 1130 17.37
40		12	(wafer adj scanner) and ((count\$3 or measur\$3) with ((dynamic adj	USPAT	2004/04/30 19:45
		ļ	particles) or particle))		
42		1	(wafer adj scanner) and ((count\$3 or measur\$3) with ((dynamic adj	USPAT	2004/04/30 19:45
	1		particles) or particle)) and photoresist		
43		95	(((count\$3 or measur\$3) with ((dynamic adj particles) or	USPAT	2004/04/30 19:50
			particle)).ti,ab,clm.) and photoresist	ļ	
44	(61	((((count\$3 or measur\$3) with ((dynamic adj particles) or	USPAT	2004/04/30 19:53
	. .		particle)) ti,ab,clm.) and photoresist) and wafer	1	
45	i ·	2	(((((count\$3 or measur\$3) with ((dynamic adj particles) or	USPAT	2004/04/30 19:51
	ŀ	ļ	particle)) ti,ab,clm.) and photoresist) and wafer) and (((silicon adj	Ī	
		ĺ	nitride) or (silicon adj oxide) or (silicon adj oxynitride) or polysilicon)		
			with etching)		·
46		2	((((((count\$3 or measur\$3) with ((dynamic adj particles) or	USPAT	2004/04/30 19:53
		- 1	particle)).ti,ab,clm.) and photoresist) and wafer) and (((silicon adj		
		-	nitride) or (silicon adj oxide) or (silicon adj oxynitride) or polysilicon)		
			with etching)) and ((count\$3 or measur\$3) with ((dynamic adj particles)		1
	,		or particle))		